

L Number	Hits	Search Text	DB	Time stamp
2	5	US-4687560-\$.DID. OR US-6126743-\$.DID. OR US-6048621-\$.DID. OR US-5286520-\$.DID. OR US-5385751-\$.DID.	USPAT; US-PGPUB	2003/11/28 18:12
3	446	float adj glass and (CVD chemical adj vapor adj deposition)	USPAT; US-PGPUB	2003/11/28 18:29
4	160	(float adj glass and (CVD chemical adj vapor adj deposition)) and tungsten	USPAT; US-PGPUB	2003/11/28 18:19
5	1	(float adj glass and (CVD chemical adj vapor adj deposition)) and tungsten adj (oxyhalide chloride oxychloride)	USPAT; US-PGPUB	2003/11/28 18:14
6	73	(float adj glass and (CVD chemical adj vapor adj deposition)) and tungsten adj oxide	USPAT; US-PGPUB	2003/11/28 18:29
7	60	((float adj glass and (CVD chemical adj vapor adj deposition)) and tungsten adj oxide) and vacuum	USPAT; US-PGPUB	2003/11/28 18:19
8	104	float adj glass and (CVD chemical adj vapor adj deposition) with vacuum	USPAT; US-PGPUB	2003/11/28 18:34
9	27	(float adj glass and (CVD chemical adj vapor adj deposition) with vacuum) and tungsten adj oxide	USPAT; US-PGPUB	2003/11/28 18:34
11	7	(float adj glass and (CVD chemical adj vapor adj deposition) with low adj pressure) and tungsten adj oxide	USPAT; US-PGPUB	2003/11/28 18:34
10	28	float adj glass and (CVD chemical adj vapor adj deposition) with low adj pressure	USPAT; US-PGPUB	2003/11/28 18:35
12	32	float adj glass and ((CVD chemical adj vapor adj deposition) with low adj pressure) LPCVD)	USPAT; US-PGPUB	2003/11/28 18:36
13	25	(float adj glass and ((CVD chemical adj vapor adj deposition) with low adj pressure) LPCVD)) not ((float adj glass and (CVD chemical adj vapor adj deposition) with low adj pressure) and tungsten adj oxide)	USPAT; US-PGPUB	2003/11/28 18:36
18	19	solar adj control same tungsten	USPAT; US-PGPUB	2003/11/28 18:51
19	1	07/806177.app.	USPAT; US-PGPUB	2003/11/28 19:10
20	2077	atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) AECVD	USPAT; US-PGPUB	2003/11/28 20:21
21	0	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) AECVD) same tungsten with chloride	USPAT; US-PGPUB	2003/11/28 20:21
22	1	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) AECVD) and tungsten with chloride	USPAT; US-PGPUB	2003/11/28 20:21
23	1	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) AECVD) and tungsten with hexachloride	USPAT; US-PGPUB	2003/11/28 20:21
24	0	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) AECVD) and tungsten with oxychloride	USPAT; US-PGPUB	2003/11/28 20:22
25	0	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) AECVD) and tungsten with oxyhalide	USPAT; US-PGPUB	2003/11/28 19:14
26	20	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) AECVD) and tungsten with fluoride	USPAT; US-PGPUB	2003/11/28 19:14
27	1	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) AECVD) and tungsten with oxyfluoride	USPAT; US-PGPUB	2003/11/28 19:14
28	2540	atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) APCVD	USPAT; US-PGPUB	2003/11/28 20:21
29	0	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) APCVD) same tungsten with chloride	USPAT; US-PGPUB	2003/11/28 20:21

30	1	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) APCVD) and tungsten with chloride	USPAT; US-PGPUB	2003/11/28 20:21
31	1	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) APCVD) and tungsten with hexachloride	USPAT; US-PGPUB	2003/11/28 20:21
32	2	(atmospher\$5 adj pressure adj (CVD chemical adj vapor adj deposition) APCVD) and tungsten with oxychloride	USPAT; US-PGPUB	2003/11/28 20:22